

Metallic ion implantation device.

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Inventor(s): BERNARDET HENRI SOCIETE CIVILE [FR]; THIEBAUT
CHANTAL SOCIETE CIVIL [FR]

Applicant(s): PHILIPS NV [NL]

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Metallurgical implanter of metal ions having a large emissive surface area, significant flux and adjustable implantation depth comprising, inside an implantation chamber kept evacuated, at least one vacuum-arc ion source (1, 2, 3, 4) from which the ions (5) are extracted and projected onto a target (9) by means of an extracting and focusing electrode (6, 7) and of an acceleration electrode (8) which are polarised to very high and to low voltage respectively. The target (9) bombarded with the ion stream emits a flux of secondary electrons which are repelled by a suppressor electrode (10) which is negatively polarised relative to the earthed target. <??>Application in metallurgy.

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